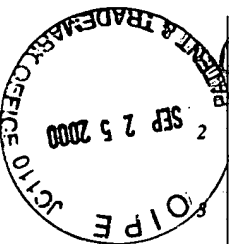


#7/ *Amoldt B*
A Ford
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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. 09/212,726
Filing Date December 15, 1998
Inventor Klaus F. Schuegraf
Assignee Micron Technology, Inc.
Group Art Unit 2813
Examiner E. Kielin
Attorney's Docket No. MI22-1098
Title: Semiconductor Processing Methods of Chemical Vapor Depositing SiO₂

RESPONSE TO JUNE 16, 2000 OFFICE ACTION

To: Assistant Commissioner for Patents
Washington, D.C. 20231

From: Bernard Berman (Tel. 509-624-4276; Fax 509-838-3424)
Wells, St. John, Roberts, Gregory & Matkin P.S.
601 W. First Avenue, Suite 1300
Spokane, WA 99201-3828

Sir:

Responsive to the Office Action dated June 16, 2000, applicant requests reconsideration of the above referenced application in view of the amendments and remarks that follow:

AMENDMENTS

In the Claims

In Claim 43, on line 4 of the claim, insert ~~at~~ at a reduced rate,-- immediately after "precursor."

In Claim 44, on line ³2 of the claim, delete "silane,."

In Claim 46, on line 2 of the claim, replace "hot" with --wall--.

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